



The temperature dependence of the time-averaged drift mobility in As₂S₃ glass derived from PA measurements

A.M Andriesh, I.P Culeac, P. J. S Ewen, A. E Owen

[https://doi.org/10.1016/S0022-3093\(98\)00197-5](https://doi.org/10.1016/S0022-3093(98)00197-5)

Abstract

The temperature dependence of the bimolecular recombination rate coefficient (b) and the time-averaged drift mobility in As₂S₃ glass was studied in the range 77–330 K on the basis of steady-state photoinduced absorption (PA) measurements. PA measurements have been carried out on glass samples in the form of optical fibres. The steady-state PA coefficient varies approximately as the square root of the excitation light intensity, indicating a bimolecular mechanism for the recombination of excess carriers. In most disordered semiconductors carrier transport is diffusion-limited and taking into account that for chalcogenide glasses the electron drift mobility $\mu_n \ll \mu_p$ the hole drift mobility, the latter was derived from $\mu_p = (\epsilon\epsilon_0/e)b$. The time-averaged mobility, μ_p , was found to be thermally activated at the higher temperatures with activation energy ~ 0.9 eV, and with $\mu_p \sim 10^{-10}$ cm²/Vs at 300 K, but almost temperature independent below approximately 130 K.